Safety Violations

Common Examples

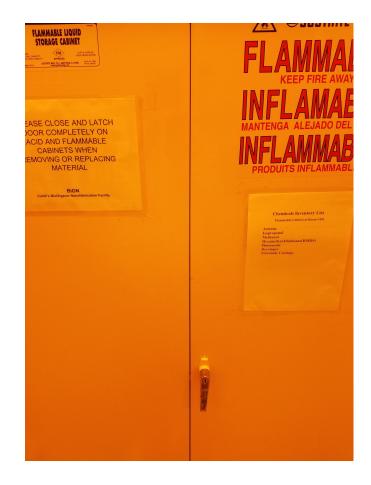
Frequently noticed violations

- Flammable cabinets not properly closed
- Illegible/Incomplete log books
- Hot Plates unattended and/or in forbidden areas
- Illegible/Incomplete process in progress and hazardous in use forms
- Microscopes lamps/lights left on
- Forged Sessions not started/stopped properly
- Trash left in the wrong trash bin
- Chemical bottles improperly stored
- Oven doors not closed properly, forbidden items found inside
- Lock Out / Tag Out tags not respected
- Chemicals left beyond their acceptable date
- Bulk chemicals not returned to flammable cabinets

Flammable cabinets not properly closed











• Hot Plates unattended and/or in forbidden areas

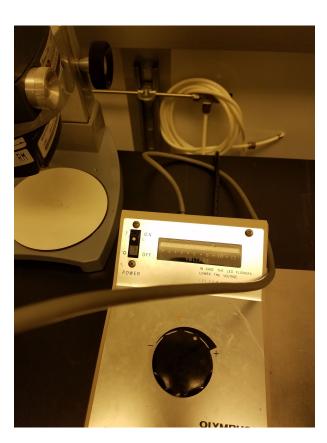


• Illegible/Incomplete process in progress and hazardous in use forms

	PROCESS IN-USE FORM			
	Name: Phone:		Na Alexandra Martina Santa Alexandra Ale	
	Name of Chemical:		Rex III	
	Other Comments:			
	HAZARDOUS IN-USE FOR	M		HAL
	• Date			AHE
	Vour Contact Info			
	NamePhone_			
	Name of the Chemical			
001	UCI Integrated Nanosystems Research Facility			



• Microscopes left on







• Trash left in the wrong trash bin



• Chemical bottles improperly stored



• Oven doors not closed properly, forbidden items found inside



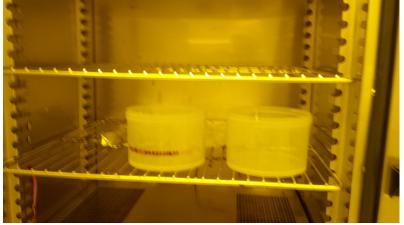


• Lock Out / Tag Out tags not respected



WET ETCH BENCH RESERVATION/SIGN-IN								
DATE	NAME	TIME IN/OUT	HF BENCH RM 1432	CLEANING BENCH RM 1421	METAL ETCH RM 1422	COMMENT		
			-					
						<u></u>		
	-							
-								
		K-						
-		,						
	NOT	// ERASE	AFTER	USE	111 + 1111	1+111		
EXAMPLE	JAKE'S CELL	(562)-522-8328	IF	YOU	HAVE	QUESTIONS		
01/01/14		11111	111111	Dillin	11/1/11			
01/01/14		:00AM-10:00AM	48% HF			ОК		
	JARE 1	2:00PM-2:00PM		C it		OK		



















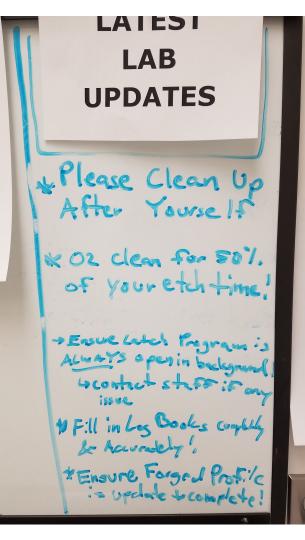


ZINRF BION POLICY OVERVIEW

- 1. All users must be familiar with the INRF Safety Policies & Procedures before entering the cleanroom.
- See our Lab Safety Manual at: http://www.inrf.uci.edu/safety/standard-procedures/
- 2. Regular work hours are 7:00a.m. 5:00 p.m. Users that require after hour access must become a Super User.
- 3. All users/guests/and staff must log in and log out of the facilities. NO EXCEPTIONS.
- 4. Once approved for use of lab tools, users must log in and out and fill out the necessary logbook information. Various tools can be reserved at the tool or by website. Only one slot can be reserved at a time. If the tool has not been booked a user can use the tool multiple slots but if another user needs the tool the current user has to give up a time slot.
- 5. Users must access the facility or tools they are approved to use on a regular basis or accessibility will be denied. If you do not access the tools within 90 days access will be denied. If you do not access the facility within 180 days accessibility will be denied.
- 6. The **buddy system is highly enforced!** It is required when performing any wet etch processing. Please communicate with one another when performing this task. Pay close attention to posted do and don't signs.
- 7. User Clothing: PPE equipment is always required to be worn when using or handling acid materials. Safety glasses should be worn at all times in the lab, except when using a microscope or other equipment with eyepieces (Exception: Those with prescription glasses – see Jake Hes for clearance)
- 8. All users are required to clean up after themselves. Example, bench tops and utensils in wet etch and developing areas and upon finishing up with spinners.
- In use chemical forms are required to identify chemicals that are presently being used. This is especially important with chemicals that are being stored on bench tops overnight or for long etch times.
- Personal chemicals need to be properly labeled and dated within 90 day intervals so staff can identify personal chemical in use. Any chemical beyond 90 days will be disposed of.



- 3. Sudden and fast movements (i.e., no running).
- 4. Wearing open toe shoes or sandals.
- 5. Working alone when handling hazardous material.
- 6. Bringing in chemicals before receiving proper approval.
- Working with chemicals in an undesignated area (must work under exhaust hood).
- 8. Installing or changing out gas cylinders.



Please RSVP to stevenm4@uci.edu and in the subject line please use "RSVP All Hands".

Thank You,

INRF Staff

Forged System Notice to Every and All UCI INRF and BiON Users

June 19, 2017

BiON, Equipment, Equipment Down, General, INRF, Maintenance / Repair, Safety

All INRF and BiON Users,

Reminder: Both INRF and BiON lab entrances are now done through the Forged System via Chrome All equipment in both the INRF and BiON are also now operated through the Forged System via Chrome. *There should be no more instances of the past Legacy System in operation, either for tools or for Lab Log in.

Please do NOT start playing around with netbooks or computers looking for the Legacy System or changing computer settings.

Please do NOT access the Latch System.

Please do NOT modify hardware (cables, latch boxes, etc).



Forged Violations Page

ノ I.N.R.F.	E 🔓 Steven Martinez	Ą	О госопт
Profile	Profile		P
Steven Martinez	Profile Card	¢	Yu-Wei Lin has finished using the Laurell 2 Spinner Jun 26, 04:59PM
	Steven Martinez Pracility Administrator	¢	Yu-Wei Lin is operating the Karl Suss MA6 Mask Aligner Jun 26, 04:47PM
Equipment > Facilities >	Phone Email (949) 343-1800 stevenm4@uciedu	(1	Dawei Wang has entered INRF Jun 26, 04:16PM
∐ Inventory > ⊥ SDS >	Bio	2	Dogukan Yildirim has exited INRF Jun 26, 04:09PM
Operations >	Violations General Notes	¢	has finished using
Calendar >	Date Submitted By Description Submitted By Note Add New Violation Add New Note Add New Note		the Karl Suss MA6 Mask Aligner Jun 26, 03:51PM
Profiles Pending Manage	06/26/2017 Description Note	¢	Yu-Wei Lin is operating the Laurell 2 Spinner Jun 26. 03:49PM
	Add Violation Add Violation Authorized Equipment	¢	Dogukan Yildirim has finished using the Laurell 2 Spinner Jun 26, 03:31PM
	SELECT EQUIPMENT Regular Hours + After Hours Add Authorized Equipment Control Contro Control Contro	¢	Yu-Wei Lin is operating the Trion Etcher for SiO2/Nitride Jun 26, 03:30PM